

Amendments to the Claims

The listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (currently amended) A ~~coating~~ method of manufacturing an aperture plate, comprising:

forming a hole having a predetermined diameter in a metal plate with etching while using resist,

cleaning the metal plate to remove the resist,

placing a the metal plate in a vacuum chamber of a chemical vapor deposition device,

charging in the vacuum chamber a mixture of a ~~gas containing at least osmium~~ sublimation gas of an osmium oxide crystal, at least one gas selected from the group consisting of an argon gas, a krypton gas and a xenon gas, and a ~~gas containing~~ a hydrogen gas, and

generating plasma inside the vacuum chamber to provide osmium coating on the metal plate.

2. (cancelled)

3. (currently amended) A ~~coating~~ method according to claim 1, wherein said metal plate is placed on a cathode facing an anode of the chemical vapor deposition device, relations among voltage for discharging plasma, a distance between the cathode and anode and a pressure of the gases in the vacuum chamber being set so that voltage for discharging plasma becomes minimum relative to product of the distance between the cathode and anode and the pressure of the gases in the vacuum chamber.

4. (currently amended) A ~~coating~~ method according to claim 1, wherein said metal plate is an aperture plate for an electron microscope having a ~~micro-hole~~ the hole therein.

5. (canceled)

6. (new) A method according to claim 1, wherein in charging the mixture in the vacuum chamber, the sublimation gas of the osmium oxide crystal is generated in a sublimating cylinder and is introduced into the vacuum chamber through a valve.

7. (new) A method according to claim 6, wherein in charging the mixture in the vacuum chamber, said at least one gas and said hydrogen gas are separately introduced into the vacuum chamber through valves.

8. (new) A method according to claim 7, wherein said plasma is generated inside the vacuum chamber at a pressure between 3 to 20 Pa.

9. (new) A method according to claim 8, wherein said gas containing the hydrogen gas is a mixture of the hydrogen gas and the argon gas, and the hydrogen gas is contained in a range between 30 to 70%.

10. (new) A method according to claim 9, wherein said metal plate is formed of molybdenum.